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(54) Title: PROCESS CHAMBER ASSEMBLY WITH REFLECTIVE HOT PLATE AND PIVOTING LID

(57) Abstract: A hot plate assembly includes a base plate, a lid and a housing positioned between the base plate and the lid. The housing, lid and base plate form a process chamber. An insulator is positioned adjacent to the base plate in the process chamber. An air gap is formed at least partially between a bottom surface of the insulator and a top surface of the base plate. A hot plate is positioned adjacent to the insulator in the process chamber. At least a first reflective member is positioned between the hot plate and the insulator.